

## **Application Data Sheet**

### **Application Information**

Application Type::	Regular
Subject Matter::	Utility
Suggested Group Art Unit::	N/A
CD-ROM or CD-R?::	None
Sequence submission?::	None
Computer Readable Form (CRF)?::	No
Title::	METHOD OF FORMING SI-CONTAINING THIN FILM
Attorney Docket Number::	09852/0200879-US0
Request for Early Publication?::	No
Request for Non-Publication?::	No
Suggested Drawing Figure::	1
Total Drawing Sheets::	2
Small Entity?::	No
Petition included?::	No
Secrecy Order in Parent Appl.?::	No

### **Applicant Information**

Applicant Authority Type::	Inventor
Primary Citizenship Country::	Japan
Status::	Full Capacity
Given Name::	Atsushi
Family Name::	Itsuki
City of Residence::	Naka-gun, Ibaraki-ken
Country of Residence::	Japan
Street of mailing address::	c/o Mitsubishi Materials Corporation, Central Research Institute Naka Research Center, 1002-14, Mukaiyama, Naka-cho

City of mailing address:: Naka-gun, Ibaraki-ken  
Country of mailing address:: Japan

**Correspondence Information**

Correspondence Customer Number:: 07278

**Representative Information**

Representative Customer Number:: 07278

**Foreign Priority Information**

Country::	Application number::	FilingDate::	Priority Claimed::
Japan	2003-034560	02/13/03	Yes
Japan	2004-005285	01/13/04	Yes

**Assignee Information**

Assignee name:: MITSUBISHI MATERIALS CORPORATION  
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City of mailing address:: Tokyo  
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